

Control of Regioselectivity in the Alkylation of 2-Trimethylsilyl-2,5-dihydrothiophene 1,1-Dioxide. A Route for 2,2-Dialkylation

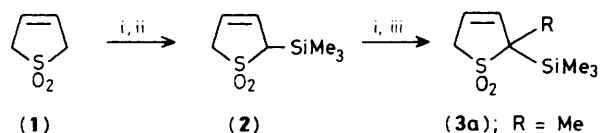
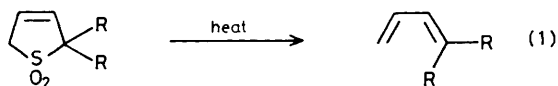
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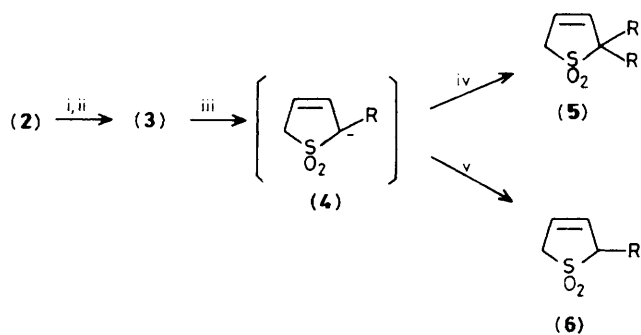
The readily available 2-trimethylsilyl-2,5-dihydrothiophene 1,1-dioxide can be converted regioselectively into the dialkyl- and dispiro analogues, which are precursors of the corresponding 1,1-disubstituted buta-1,3-dienes and asymmetric dicycloalkylideneethanes, respectively.

During studies of the synthetic applications of the direct deprotonation-alkylation reaction of 2,5-dihydrothiophene 1,1-dioxides,¹ we and others have found that one-pot or stepwise dialkylation reactions regioselectively give the 2,5-disubstituted analogues,² but regioselective control of 2,2-dialkylation directly from (1) has never been achieved. The thermolysis of the 2,2-disubstituted products to give the corresponding disubstituted buta-1,3-dienes is well established, (reaction 1).³ We hereby describe an attractive and convenient method for the synthesis of these compounds from the 2-trimethylsilyl derivative (2).

Compound (2) was synthesized in 43% yield by treatment of the anion of (1) with $\text{Me}_3\text{SiCl-NaI}$ in tetrahydrofuran (THF)-hexamethylphosphoramide (HMPA).⁴ The yield can be improved to 70% by using Me_3SiI in THF (Scheme 1). When (2) in THF was treated with Bu^nLi (1 equiv., -105°C) and then with MeI (1 equiv.), the 2-methyl-2-trimethylsilyl analogue (3a) was produced in 85% yield (Scheme 1). If 2.5 equiv. of MeI were used and HMPA was added as cosolvent in the same sequence, (3a) was formed along with the 2,2-dimethyl compound (5a) and the 2-methyl compound (6a) in

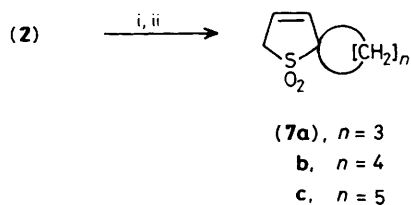


Scheme 1. Reagents and conditions: i, Bu^nLi , THF, -105°C ; ii, Me_3SiI ; iii, MeI (1 equiv.).

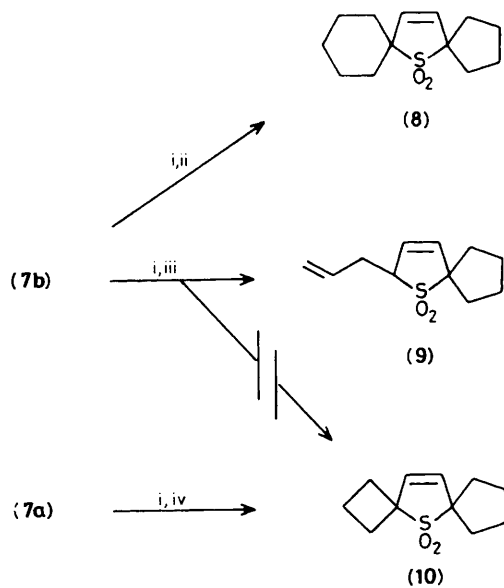


a; R = Me
b; R = Et

Scheme 2. Reagents and conditions: i, Bu^nLi , THF-HMPA, -105°C ; RI (2.5 equiv.); iii, I^- ; iv, RI; v, H_2O .



Scheme 3. Reagents and conditions: i, BuⁿLi, THF-HMPA, -105 °C; ii, I-[CH₂]_n-I, -105 °C reflux.



Scheme 4. Reagents and conditions: i, LiHMDS, THF-HMPA, -78 °C; ii, I-[CH₂]₅-I; iii, I-[CH₂]₃-I; iv, I-[CH₂]₄-I.

2:1:1 ratio. No starting material or other products were found in any significant quantity (Scheme 2). Compounds (5a) and (6a) must be formed by a second methylation or a protonation, respectively, from anion (4a) generated by iodide attack on the trimethylsilyl group of (3a).

On refluxing the reaction mixture overnight, (5a) was obtained as the major product in 52% yield. With EtI in place of MeI, (5b) was formed in 61% yield. Using an α,ω -diiodoalkane as the alkylating agent, spiro compounds (7a) (47%), (7b) (52%), or (7c) (56%) could also be produced (Scheme 3). However, a similar reaction with 1,2-diiodoethane proved to be complex and no cyclized product was observed. Further intramolecular dialkylations of (7a,b,c) with other α,ω -diiodoalkanes were expected to yield asymmetric dispirocyclic products. Since dicyclohexylidene-ethane is known to be produced in quantitative yield by the thermolysis of the symmetrical 7-thiadispiro[5.1.5.2]pentadec-14-ene 7,7-dioxide,² it was reasonable to expect the asymmetric dispirocyclic compounds to be precursors of asymmetric dicycloalkylidene-ethanes. When (7b) in THF-HMPA was treated with lithium hexamethyldisilazide (LiHMDS) (2 equiv.) and 1,5-diiodopentane (1 equiv.), the asymmetric dispirocyclic compound (8) was produced in 61% yield (Scheme 4). Interestingly, the reaction of (7b) with 1,3-diiodopropane resulted in the formation of the elimination product (9) instead of the dispiro-compound (10) (Scheme 2). However, (10) was obtained in 65% yield by the reaction of (7a) with 1,4-diiodobutane.

We thank the National Science Council of the Republic of China for financial support.

Received, 12th January 1987; Com. 028

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